



**PATENT**  
Docket No. 150.0056 0102

#15/F  
as  
5/14/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Whonchee Lee et al. ) Group Art Unit: 1765

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### Group Art Unit:

1765

Serial No.: 09/560,268 ) Examiner: Deo, Duy Vu

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Examiner:

Deo, Duy Vu

Confirmation No.: 2517

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Filed: 26 April 2000

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For: COMPOSITION FOR SELECTIVELY ETCHING AGAINST COBALT  
SILICIDE (As Amended)

## **AMENDMENT AND RESPONSE**

RECEIVED

MAY 13 2002

TC 1700

Assistant Commissioner for Patents  
Washington D.C. 20231

Dear Sir:

In response to the Office Action dated 4 February 2002, please amend the application as follows:

**In the Claims**

Please add new claims 94-96. The new claims are provided below. For convenience, all pending claims are provided in Appendix A.

94. (New) An etching composition, the composition comprising a mineral acid, a peroxide, and deionized water at a ratio in a range of about 1:1:35 (mineral acid:peroxide:deionized water) to about 1:1:5 (mineral acid:peroxide:deionized water), wherein the mineral acid is selected from the group consisting of HCl diluted to 37% by weight in deionized water, HNO<sub>3</sub> diluted to 70% by weight in deionized water, H<sub>2</sub>SO<sub>4</sub> diluted to 96% by weight in deionized water, H<sub>3</sub>PO<sub>4</sub> diluted to 85% by weight in deionized water, and HF diluted to 49% by weight in deionized water, wherein the peroxide is selected from the group consisting of hydrogen peroxide diluted to 29% by weight in deionized water, and ozone.

05/10/2002 GTEFFERA 00000138 09560268

01 FC:103  
02 FC:102